Figure (a) shows the C/S ratio of kinetic energy (eV) for Original silicon and Original mesa. The x-axis represents kinetic energy in eV, ranging from 460 to 540 eV. The y-axis shows the C/S ratio ranging from $-2 \times 10^{-4}$ to $2 \times 10^{-4}$.

Figure (b) displays the oxygen concentration (%) as a function of depth (nm) for Original silicon, Original mesa, HF, and HF+KOH treatments. The x-axis represents depth in nm, ranging from 0 to 4 nm, while the y-axis shows oxygen concentration ranging from 0 to 70%.